

Basic Specifications:

Model: XU-ACP330-R00 (SEMISTAR-PER1130)

| Item | | Specifications |
|--------------------------------|--------------|--|
| Wafer size | | 300 mm |
| Fiducial Recognition | | Notch |
| Wafer Material | | Silicon or Quartz *1 |
| Light source of sensor | | RED LED |
| Alignment accuracy *2 | Rotation | $\pm 0.1^\circ$ |
| | Wafer center | ± 0.1 mm |
| Alignment time *3 | | Less than 5.0 sec |
| Motion Range | | Mechanical motion range : No hard stop (unlimited) (With soft ware motion stop) Lifter part stroke: 17mm Grip part stroke: 4mm |
| Capture range | | 304mm |
| Clean Class | | ISO Class1 *4 |
| Wafer holding method | | Active edge grip method |
| Wafer detection | | CCD Line sensor |
| Motor | | AC servo motor with 20 bit Incremental Encoder (AC200V) |
| Detection of rotation position | | Absolute encoder of a motor. There is battery for encoder backup in the body. |
| CDA requirement | | 0,21 to 0,22 MPa (30,45 to 31,9 psi) 1,5L/min |
| Vacuum requirement | | -80 to -70 kPa, 5L/min |
| Approx. mass | | 8,8 kg |

*1 The threshold value setting for the sensor is required to be reset for quartz wafers of specified user.

*2 It is a value in SEMI standard wafer. A wafer material is silicon and edge presupposes that it is smooth.

*3 Alignment time does not include

- Un-grip and lift up time when Pre-aligner grips wafer notch.
- Operation for avoiding the interference in the case of overlapping the operation domain of grips and lift

*4 It is based on measurement in Yaskawa's clean booth. Evaluation is performed above wafer in the environment of down flow 0.3 m/ sec.

Exterior

Wafer Grip: PEEK

Lift pad: PEEK

Pre Aligner Body: Anodized Aluminum and Stainless Steel.